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In the Claims:

1. An abrasive composition for polishing substrates comprising:

a plurality of abrasive particles comprising a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 20 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

- 2. An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 15% by volume of the abrasive particles.
- 3. An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 10% by volume of the abrasive particles.
- 4. An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 15% by volume of the abrasive particles.
- 5. An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume being about 20 nanometers to about 100 nanometers, a span

value, by volume, being greater than or equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

- 6. An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 20 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.
- 7. An abrasive composition according to claim 1, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.
- 8. An abrasive composition according to claim 1, wherein said abrasive particles comprise silica.
- 9. An abrasive composition according to claim 1, wherein said abrasive particles comprise colloidal silica.
- 10. An abrasive composition according to claim 1, wherein said abrasive particles comprise, alumina, aluminum, ammonia or potassium cations bonded thereto.
- 11. An abrasive slurry composition for polishing substrates comprising:
 a plurality of abrasive particles comprising a polydisperse particle
 size distribution with median particle size, by volume, being about 20
 nanometers to about 100 nanometers, and a span value, by volume, being
 greater than or equal to 20 nanometers, wherein a fraction of said particles

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greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles; and

a solution having one or more chemical reactants.

- 12. An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 10% by volume of the abrasive particles.
- 13. An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.
- 14. An abrasive slurry according to claim 11, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.
- 15. An abrasive slurry according to claim 11, wherein said abrasive particles comprise silica.
- 16. An abrasive slurry according to claim 11, wherein said abrasive particles comprise, alumina, aluminum, ammonia or potassium cations bonded thereto.
- 17. A method for polishing substrates with an abrasive composition comprising:

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providing a substrate to be polished;

and polishing the substrate using a plurality of abrasive particles comprising, a polydisperse particle size distribution with median particle size, by volume, being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 20 nanometers, and wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.

- 18. A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 10% by volume of the abrasive particles.
- 19. A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 18 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.
- 20. A method according to claim 17, wherein said abrasive particles comprise a polydisperse particle size distribution with median particle size, by volume being about 20 nanometers to about 100 nanometers, a span value, by volume, being greater than or equal to about 15 nanometers, wherein a fraction of said particles greater than about 100 nanometers is less than or equal to about 20% by volume of the abrasive particles.
- 21. A method according to claim 17, wherein said abrasive particles comprise silica.
- 22. A method according to claim 17, wherein said abrasive particles comprise, alumina, aluminum, ammonia or potassium cations bonded thereto.